

COMPLETION FLUIDS & ADDITIVES PRODUCT

OXBAN OXYGEN SCAVENGER

Oxygen Scavenger

OVERVIEW

OxBan oxygen scavenger is a specially formulated concentrated inorganic sulfite solution.

APPLICATIONS

OxBan oxygen scavenger should be added to the suction pit with minimal agitation to avoid air entrapment. OxBan oxygen scavenger can also be dispensed by first mixing it into a drum of fresh water which is then fed into the suction pit gradually during circulating operations. A concentration should be chosen so the metered volume will be used in a 24 hour period. This will ensure a fresh makeup product daily. A 15% to 20% solution is recommended for typical operations.

FEATURES AND BENEFITS

- ▶ Rapid acting liquid oxygen scavenger.
- ▶ Integral component for corrosion control of low density clear brine fluids.
- ▶ Compatible with and soluble in seawater, sodium and potassium clear brine fluids.

RECOMMENDED TREATMENT

- ▶ The recommended treatment rate for OxBan oxygen scavenger is 1.0 to 2.0 gal/100 bbl., depending upon the dissolved oxygen content in the fluid.

SAFETY AND HANDLING

- ▶ Please refer to the product's Safety Data Sheet.

PHYSICAL PROPERTIES

Appearance

Clear, pale green-yellow liquid

Specific Gravity

1.3-1.41 @ 68°F (20°C)

Water Solubility

Soluble

PACKAGING INFORMATION

5 gal container



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